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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/676,304	09/30/2003	You-Seung Jin	9898-302	. 8176
7590 11/01/2004 MARGER JOHNSON & McCOLLOM, P.C. 1030 S.W. Morrison Street Portland, OR 97205			EXAMINER	
			ABRAHAM, FETSUM	
			ART UNIT	PAPER NUMBER
			DATE MAILED: 11/01/2004	4

Please find below and/or attached an Office communication concerning this application or proceeding.

		an e
	Application No.	Applicant(s)
Office Action Summary	10/676,304	JIN ET AL.
Office Action Summary	Examiner	Art Unit
The MAILING DATE of this communication of	Fetsum Abraham	2826
The MAILING DATE of this communication a Period for Reply	appears on the cover sheet with	n tne correspondence address
A SHORTENED STATUTORY PERIOD FOR REF THE MAILING DATE OF THIS COMMUNICATION - Extensions of time may be available under the provisions of 37 CFR after SIX (6) MONTHS from the mailing date of this communication. - If the period for reply specified above is less than thirty (30) days, a r - If NO period for reply is specified above, the maximum statutory peri - Failure to reply within the set or extended period for reply will, by stat Any reply received by the Office later than three months after the ma earned patent term adjustment. See 37 CFR 1.704(b).	N. 1.136(a). In no event, however, may a repreply within the statutory minimum of thirty od will apply and will expire SIX (6) MONT tute, cause the application to become ABA	oly be timely filed (30) days will be considered timely. HS from the mailing date of this communication. NDONED (35 U.S.C. § 133).
Status	•	
 1) ⊠ Responsive to communication(s) filed on 12 2a) ☐ This action is FINAL. 2b) ⊠ TI 3) ☐ Since this application is in condition for allow closed in accordance with the practice under 	his action is non-final. wance except for formal matte	• •
Disposition of Claims		
4) ☐ Claim(s) 1-8 and 17-19 is/are pending in the 4a) Of the above claim(s) is/are withd 5) ☐ Claim(s) is/are allowed. 6) ☐ Claim(s) all is/are rejected. 7) ☐ Claim(s) is/are objected to. 8) ☐ Claim(s) are subject to restriction and	Irawn from consideration.	
Application Papers		
9)☐ The specification is objected to by the Exami	iner.	
	ccepted or b) objected to b	
Applicant may not request that any objection to the		, ,
Replacement drawing sheet(s) including the corn 11) The oath or declaration is objected to by the	· - ·	• • •
,		
Priority under 35 U.S.C. § 119		
12) Acknowledgment is made of a claim for forei a) All b) Some * c) None of: 1. Certified copies of the priority docume 2. Certified copies of the priority docume 3. Copies of the certified copies of the priority docume application from the International Bure	ents have been received. ents have been received in Ap riority documents have been r	plication No
* See the attached detailed Office action for a li		eceived.
Kalal		
Attachment(st		
1) Notice of References Cited (PTO-892) 2) Notice of Draftsperson's Patent Drawing Review (PTO-948) 3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/C Paper No(s)/Mail Date	Paper No(s)	mmary (PTO-413) /Mail Date ormal Patent Application (PTO-152)

DETAILED ACTION

The election made on 8/12/094 has been acknowledged and approved. The nonelected claims have been withdrawn from consideration.

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(a) the invention was known or used by others in this country, or patented or described in a printed publication in this or a foreign country, before the invention thereof by the applicant for a patent.

Claims 1-4,17 are rejected under 35 U.S.C. 102(a) as being anticipated by the prior art of figure 1 in the application. Figure 1 discloses a MOSFET comprising a substrate (100) having a first thick region and a relatively thin second region, a gate insulation layer (110) formed on the first region, a gate electrode (120) on the gate insulation, epitaxial layers (150, 160) formed on the second region with predetermined thickness, spacers formed on the sidewalls of the gate electrode and part of the upper surface of the epitaxial layers, lightly doped regions (150) formed below the spacers in the epitaxial layers, and heavily doped regions (160) in a portion of the substrate exposed by the spacers.

As for claim 2, the layers are silicon.

As for claims 3,4, the sum of the thickness of the epitaxial layer and the second region is greater than the thickness of the first region.

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the

invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

Claims 5,6,8,18,19 are rejected under 35 U.S.C. 103(a) as being unpatentable over the same prior art.

Although the dimensions of the layers in the prior art are unknown, it would have been obvious to one skilled in the art to relate them to the clamed dimensions since layer thickness is a variable element that changes from a structure to another heavily depending on processing time, diffusion or epitaxial temperature and layer conductance.

As for claim 6, polysilicon for gate electrodes is notoriously known in the art to be an alternate material to metals and silicon dioxide for gate insuylation of MOSFETs, the most basic in the art.

Claim 7 is rejected under 35 U.S.C. 103(a) as being unpatentable over the same prior art in view of Tsai et al (5,648,287).

Although the prior art omits double-layered sidewalls in the MOSFET, the secondary reference shows the missing element in the same structure in the front page. Therefore, it would have been obvious to one skilled in the art to utilize double sidewalls in the prior art and in any other MOSFET since that better protects the gate from crosstalk induced problems.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Fetsum Abraham whose telephone number is: 571-272-1911. The examiner can normally be reached on 8:00 - 18:00.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Nathan J Flynn can be reached on 571-272-1915.

Fetsum Abraham

10/27/04